

 <b>UTM</b> UNIVERSITI TEKNOLOGI MALAYSIA	<b>PUSAT PENGURUSAN MAKMAL          UNIVERSITI (PPMU)</b>	Form Num.	UIRL/F/133
		Version	1/2024
		Effective Date	01/03/2024
		Equipment	PECVD
		Sample Serial No.	
<b>MICRONANO FABRICATION &amp; MACHINING LABORATORY</b>			
<b>SAMPLE SUBMISSION FORM (INDUSTRY)</b>			

**General Rules and Requirements:**

1. All information provided should be true
2. Booking will be notified/updated by email
3. Booking procedure
  - a. Submit the completed application form to UIRL Sample Acceptance Counter
  - b. **Fast Lane is offered to non-UTM customers with an additional 50% charge from the normal price**
4. Sample Condition & Preparation
  - a. **PPMU has the right to cancel any analysis if the sample is suspected to have a high risk to the safety of the operator or can cause damage to the instrument during the analysis. The cost of damages will be borne by the customer.**
  - b. **The remaining samples will be disposed of within a month after the analysis is completed.**
5. All enquiries regarding PECVD should be forwarded to the Science Officer (Mrs Nurnazmin Mohd Nordin, email: [nurnazmin@utm.my](mailto:nurnazmin@utm.my) or Assistant Engineer, Mr Muhammad Sulaiman Muhammad Zain, email: [m.sulaiman@utm.my](mailto:m.sulaiman@utm.my), tel: 07-5557729) or visit our website at [ppmu.utm.my](http://ppmu.utm.my).

1. APPLICANT'S PERSONAL PARTICULARS										
Name of Applicant										
Hand Phone No.										
Email										
Department/Division										
Signature & Official Stamp		*A digital signature is not recommended. Any matters raised in the future are beyond our responsibilities								
2. COMPANY DETAILS										
Name										
Registration No.										
Address										
Telephone No.										
Email										
Mode of Payment		Cash		EFT		Invoice		Fast Lane		
3. SAMPLE INFORMATION										
Total No. of Sample / Material										
Recipe Input		Substrate Temp. (°C)		Working Pressure (mTorr)		Process Time (sec)				
		Stable Time (°C)		RF Power (W)		Purge Time (sec)				
		Gases (sccm)								
		HiQ N <sub>2</sub>		Ar		N <sub>2</sub> O		NH <sub>3</sub>		
		GN <sub>2</sub>		SF <sub>6</sub>		SiH <sub>4</sub>		O <sub>2</sub>		
Solvent (ml)		SU-8 2002	SU-8 Developer	KMPR 1035	AZ IPS-6090 PR					
		SU-8 2010	Remover PG	AZ 1505 PR	AZ nLOF 2070 Negative Resist					
		SU-8 2075	AZ 40 XT – 11 D	Isopropanol	Acetone					
		AZ 826 MIF Developer	Technistrip P1316	Ethanol						
Remarks										